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H01L 21/22**(21)Application number : **01-222542**(71)Applicant : **SHINETSU SEKIEI KK**(22)Date of filing : **29.08.1989**(72)Inventor : **FUJINOKI AKIRA
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SUZUKI NOBORU****(54) SYNTHETIC QUARTZ GLASS MEMBER HAVING EXCELLENT HEAT RESISTANCE**

(57)Abstract:

PURPOSE: To contrive to improve the stain and heat resistances of a synthetic quartz glass member by adding Al to a highly pure synthetic quartz glass.

CONSTITUTION: An inert gas carrying sublimed gas prepared by heating anhydrous $AlCl_3$ is fed into an oxygen hydrogen flame hydrolyzing $SiCl_4$ and the produced soot-like silica fine particles are deposited on a substrate to prepare an Al-containing porous glass base material having an Al content of 0.5-20ppm. The glass base material is, if necessary, heated in a nitrogenizing agent (e.g. ammonia) at 700-900°C to add 100-4000ppm of the nitrogen to glass base material and subsequently heated in an inert atmosphere at 1300-1500°C to provide transparent glass.

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